

Inventor: Theodore M. Taylor

Title: Methods of Forming Spaced Conductive Regions, and Methods of Forming Capacitor Constructions

Assignee: Micron Technology, Inc.

INFORMATION DISCLOSURE STATEMENT
PURSUANT TO 37 C.F.R. " 1.56, 1.97 AND 1.98

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. No admission is made regarding whether all the submitted references are prior art.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a continuation application of co-pending application Serial No. 10/177,054, filed June 21, 2002. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. § 1.98(d) and MPEP § 609(2).

Citation of these references is respectfully requested.

Dated: 2/17/04

Respectfully submitted,

By: David G. Latwesen, Ph.D.

Reg. No. 38,533

Form PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
MI22-1504SERIAL NO.
10/177,054LIST OF ART CITED BY APPLICANT
(Use several sheets if necessary)APPLICANT
Theodore M. Taylor et al.FILING DATE
Filed HerewithGROUP
Unknown

U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	6,458,654 B1	10-2002	Claimpitt			
	AB	6,171,902	01-2001	Ida			
	AC	6,037,212 A	03-2000	Chao			
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AM							
	AN							
	AO							
	AP							
	AQ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

	AR		
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EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.